



视图比例 2:1

NOTES

1. OPERATION WAVELENGTH: 532 nm
2. CLEAR APERTURE: >80%CA
3. AR COATING(S1,S2,S3,S4):  $R_{avg} < 0.25\%$  @532 nm(6° AOI,SINGLE SURFACE)
4. ANGLE TOLERANCE:  $\pm 1'$
5. COATING(S5):  $T_p > 95\%$ ,  $R_s > 99.5\%$
6. GLUED(S5,S6): NOA61
7. EXTINCTION RATIO( $T_p:T_s$ ): >3000:1
8. TRANSMITTED BEAM DEVIATION:  $0^\circ \pm 5$  arcmin
9. REFLECTED BEAM DEVIATION:  $90^\circ \pm 5$  arcmin
10. SURFACE QUALITY(S1,S2,S3,S4): 40/20(S/D)
11. WAVEFRONT ERROR(RMS):  $\lambda/4@633$  nm
12. SURFACE FLATNESS(S1,S2,S3,S4):  $\lambda/4@633$  nm
13. OTHER SURFACES: FINE GROUND
14. CHAMFER: 0.2 mm,45°

DRAWING PROJECTION			<b>LBTEK</b>			
	NAME	DATE				
DRAWN	LTAN	Aug./31st/25	LASER LINE POLARIZATION BEAM SPLITTER L=12.7 mm, $T_p:T_s > 3000:1@532$ nm			
APPROVAL	WCHENG	Aug./31st/25	MATERIAL	WEIGHT	SCALE	REV
FOR INFORMATION ONLY NOT FOR MANUFACTURING PURPOSES			UVFS	4.5 g	4:1	C